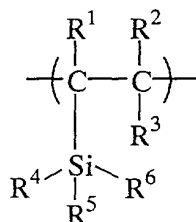


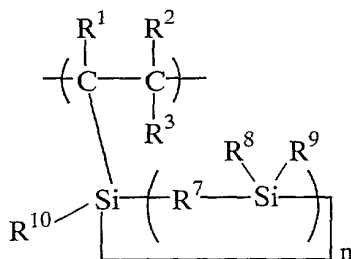
CLAIMS:

1. A silicon-containing polymer comprising recurring units of at least one of the following general formulae (1) and (2):



(1)

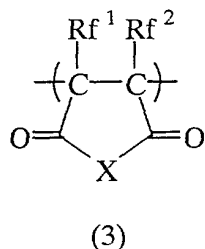
wherein R¹, R² and R³ each are hydrogen or a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, R⁴, R⁵ and R⁶ each are independently an alkyl or haloalkyl group having 1 to 20 carbon atoms, an aryl group having 6 to 20 carbon atoms or a silicon-containing group attached to the silicon atom through a siloxane or silalkylene linkage,



(2)

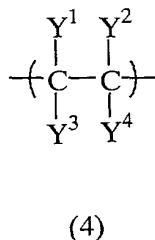
wherein R¹ to R³ are as defined above, R⁷ is an oxygen atom,
15 a straight, branched or cyclic alkylene group of 1 to 10
carbon atoms or an arylene group, R⁸ to R¹⁰ each are
independently a straight, branched or cyclic alkyl or
fluorinated alkyl group having 1 to 10 carbon atoms or an
aryl group, and n is an integer of 2 to 10.

2. The silicon-containing polymer of claim 1 further comprising recurring units of the general formula (3):



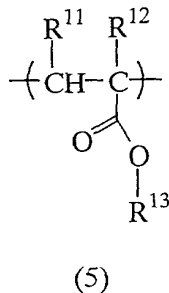
wherein X is an oxygen atom, a sulfur atom or -NR-, R is hydrogen, hydroxyl, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, or an aryl group, and may contain an acid labile group, Rf¹ and Rf² each are independently hydrogen, fluorine or trifluoromethyl.

3. The silicon-containing polymer of claim 1 further comprising recurring units of the general formula (4):



wherein Y¹, Y², Y³ and Y⁴ are independently selected from the class consisting of hydrogen, fluorine, chlorine, bromine, cyano, alkoxy carbonyl, fluorinated alkyl and fluorinated alkoxy carbonyl groups.

4. The silicon-containing polymer of claim 1 further comprising recurring units of the general formula (5):



wherein R¹¹ and R¹² each are hydrogen or a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, and R¹³ is an acid labile group or adhesive group.

5 5. A resist composition comprising the polymer of claim 1.

6. A chemically amplified, positive resist composition comprising

- 10 (A) the polymer of claim 1,
(B) a photoacid generator, and
(C) an organic solvent.

7. The resist composition of claim 6 further comprising
(D) a dissolution inhibitor.

15 8. The resist composition of claim 6 further comprising
(E) a basic compound.

20 9. A process for forming a resist pattern comprising the steps of:

applying the resist composition of any one of claims 5 to 8 onto a substrate to form a resist layer,

25 heat treating the resist layer and then exposing it to high-energy radiation having a wavelength of up to 300 nm or electron beam through a photo mask, and

optionally heat treating the exposed resist layer and developing it with a developer.

30 10. A process for forming a resist pattern comprising the steps of:

applying the resist composition of any one of claims 5 to 8 onto a processable substrate formed on a support substrate through an organic film to form a resist layer,

35 heat treating the resist layer and then exposing it to high-energy radiation having a wavelength of up to 300 nm or electron beam through a photo mask,

optionally heat treating the exposed resist layer and developing it with a developer, and

treating the organic film and the processable substrate by an etching process including oxygen plasma etching at the portions where the exposed resist layer portions are removed by developing.

11. The process of claim 10 wherein the organic film is a novolac resin or polyhydroxystyrene layer.

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12. A process for forming a resist pattern comprising the steps of:

applying the resist composition of any one of claims 5 to 8 onto a processable substrate formed on a support substrate to form a resist layer,

heat treating the resist layer and then exposing it to high-energy radiation having a wavelength of up to 300 nm or electron beam through a photo mask,

optionally heat treating the exposed resist layer and developing it with a developer, and

treating the processable substrate by an etching with a halogen gas containing chlorine or bromine at the portions where the exposed resist layer portions are removed by developing.